

Docket No. 217218US2PCT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

IN RE APPLICATION OF: Marc DELAUNAY, et al.

SERIAL NO: 10/019,278

GAU: 1762

FILED: January 2, 2002

EXAMINER: MARKHAM, WESLEY D.

FOR: METHOD AND DEVICE FOR ELECTRONIC CYCLOTRONIC RESONANCE PLASMA ...



INFORMATION DISCLOSURE STATEMENT UNDER 37 CFR 1.97

COMMISSIONER FOR PATENTS  
ALEXANDRIA, VIRGINIA 22313

SIR:

Applicant(s) wish to disclose the following information.

REFERENCES

- ☒ The applicant(s) wish to make of record the references listed on the attached form PTO-1449. Copies of the listed references are attached, where required, as are either statements of relevancy or any readily available English translations of pertinent portions of any non-English language references.
- ☒ A check or credit card payment form is attached in the amount required under 37 CFR §1.17(p).

RELATED CASES

- ☐ Attached is a list of applicant's pending application(s) or issued patent(s) which may be related to the present application. A copy of the patent(s), together with a copy of the claims and drawings of the pending application(s) is attached along with PTO 1449.
- ☐ A check or credit card payment form is attached in the amount required under 37 CFR §1.17(p).

CERTIFICATION

- ☐ Each item of information contained in this information disclosure statement was first cited in any communication from a foreign patent office in a counterpart foreign application not more than three months prior to the filing of this statement.
- ☐ No item of information contained in this information disclosure statement was cited in a communication from a foreign patent office in a counterpart foreign application or, to the knowledge of the undersigned, having made reasonable inquiry, was known to any individual designated in 37 CFR §1.56(c) more than three months prior to the filing of this statement.

DEPOSIT ACCOUNT

- ☒ Please charge any additional fees for the papers being filed herewith and for which no check or credit card payment is enclosed herewith, or credit any overpayment to deposit account number 15-0030. A duplicate copy of this sheet is enclosed.

Respectfully submitted,

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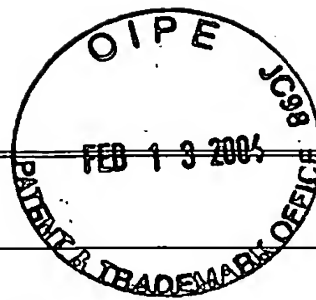
Ronald A. Rudder, Ph.D.

Registration No. 45,618

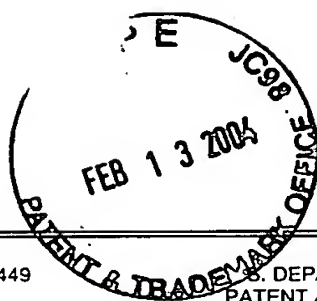
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Form PTO 1449 (Modified)		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY DOCKET NO. 217218US2PCT		SERIAL NO. 10/019,278	
LIST OF REFERENCES CITED BY APPLICANT				APPLICANT Marc DELAUNAY, et al.			
				FILING DATE January 2, 2002		GROUP 1762	
U.S. PATENT DOCUMENTS							
EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
	AA						
	AB						
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FOREIGN PATENT DOCUMENTS							
		DOCUMENT NUMBER	DATE	COUNTRY	TRANSLATION YES NO		
	AO						
	AP						
	AQ						
	AR						
	AS						
	AT						
	AU						
	AV						
OTHER REFERENCES (Including Author, Title, Date, Pertinent Pages, etc.)							
	AW	A.Y. Tcherepanov et al, Flat Panel Displays Based Upon Low-Voltage Carbon Field Emitters, 7 <sup>th</sup> International Vacuum Microelectronics Conference, July 1994, vol. 50, pgs. 205-208.					
	AX	D. Hong et al., Field Emission From P-Type Polycrystalline Diamond Films, 7 <sup>th</sup> International Vacuum Microelectronics Conference, Number 271, April 1994, pgs. 96-99.					
	AY	M. Delaunay et al, Electron Cyclotron Resonance Plasma Ion Source for Material Depositions, Review of Scientific Instruments, vol. 69, Number 6, June 1998, pgs. 2320-2324.					
	AZ	Seiichiro Matsumoto, Chemical Vapour Deposition of Diamond in RF Glow Discharge, Journal of Materials Science Letters 4, 1985, pgs. 600-602.				<input checked="" type="checkbox"/> Additional References sheet(s) attached	
Examiner					Date Considered		
*Examiner: Initial if reference is considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.							



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OTHER REFERENCES (Including Author, Title, Date, Pertinent Pages, etc.)					
	AAA	Jean-Michel Le Corfec, La television du futur se met à plat, Physique Comprendre, April 1998, pg. 87.			
	AAB	Sumio Iijima, Helical Microtubules of Graphitic Carbon, Letters to Nature, Vol. 354, November 7, 1991, pgs. 56-58.			
	AAC	Olivier M. Kuteel, et al., Electron Field Emission From Phase Pure Nanotube Films Grown in a Methane/Hydrogen Plasma, Applied Physics Letters, vol. 73, Number 15, October 12, 1998, pgs. 2113-2115.			
	AAD	Z.P. Huang, et al., Growth of Highly Oriented Carbon Nanotubes by Plasma-Enhanced Hot Filament Chemical Vapor Deposition, Applied Physics Letters, Vol. 73, Number 26, December 28, 1998, pgs. 3845-3847.			
	AAE	Li Yunjun et al, Field Electron Emission From Highly Graphitic Diamond Films With Ball-Like Surface Morphologies, Technical Digest of International Vacuum Microelectronics Conference, Kyomgiu, Korea August 1997, pgs. 137-140.			
	AAF	W.Z. Li et al, Large-Scale Synthesis of Aligned Carbon Nanotubes, Reports, Science, vol. 274, December 6, 1996, pgs. 1701-1703.			
	AAG	M. Delaunay et al., Electron Cyclotron Resonance Plasma Ion Source For Material Depositions, Review of Scientific Instruments, Vol. 69, Number 6, June 1998, pgs. 2320-2324.			
	AAH	Yahachi Saito et al., High Yield of Single-Wall Carbon Nanotubes by arc Discharging Using Rh-Pt Mixed Catalysts, Chemical Physics Letters Vol. 294, September 25, 1998, pgs. 593-598.			
	AAI	S.P. Bozeman et al., Electron Field Emission From Amorphous Carbon-Cesium Alloys, J. Vac. Science Technol. A 15(3), May/June 1997, pgs. 1729-1732.			
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	AAK	Gehan A.J. Amaratunga et al., Nitrogen Containing Hydrogenated Amorphous Carbon for Thin-Film Field Emission Cathodes, Appl. Phys. Letters 68 (18), 29 April 1996, pgs. 2529-2531.			
	AAL	B.S. Satyanarayana et al., Field Emission From Tetrahedral Amorphous Carbon, Appl. Phys. Letters, 71 (10), 8 September 1997, pgs. 1430-1432.			
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	AAO	Takuya Yara et al., Fabrication of Diamond Films at Low Pressure and Low-Temperature by Magneto-Active Microwave Plasma Chemical Vapor Deposition, Jpn. J. Appl. Phys. Vol. 33 (1994) pgs. 4404-4408.			
	AAP	C J Erickson et al., High-Sensitivity Absorption Spectroscopy on a Microwave Plasma-Assisted Chemical Vapour Deposition Diamond Growth Facility, Plasma Sources Sci. Techno. 5 (1996) pgs. 761-764.			
	AAQ				
Examiner				Date Considered	
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